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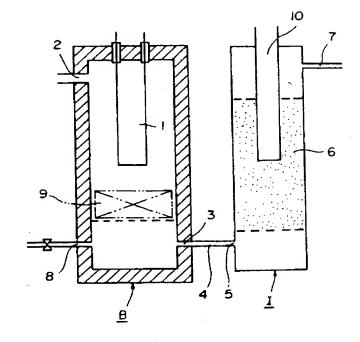
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TITLE

: MANUFACTURE OF

TRICHLOROSILANE



ABSTRACT :

PURPOSE: To manufacture SiHCl₃ in a high yield of starting materials by passing a mixed reactive gas through a metallic Si layer to convert contained harmful HCl into SiHCl₃ when SiHCl₃ is manufactured by using SiCl₄ and H₂.

CONSTITUTION: SiCl₄ is mixed with H₂ in 4:1~1:10 molar ratio and introduced into the 1st reactor B, and by electrifying a graphite resistance 1, the interior of the reactor B is heated to 500~1,300°C to produce SiHCl₃ as well as to produce HCl as a by-product in the presence of catalyst 9. This mixed gas contg. the residual unreacted SiCl₄ and H₂ is introduced into the 2nd reactorl, and while cooling the gas to 200~700°C with a cooling pipe 10 and passing it through a fixed metallic Si bed 6, the HCl is converted into SiHCl₃ by a reaction with the metallic Si. The resulting mixed gas of H2, SiCl4 and SiHCl3 is taken out of the exhaust port 7, and the SiHCl₃ is separated and collected. Since HCl is not contained, an HCI separator is unnecessary, and HCI is converted into SiHCI₃ by a reaction with Si to increase the production of SiHCl₃.

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